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	INF	ORMATION DIS	SCLO	SURE	Application Number	10/725,083	/	<u> </u>
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	Dat	e Submitted: Ap	ıril 15	2005	First Named Inventor	Tadahiro OHMI	APR 1 5 2015	
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U.S. PATENT DOCUMENTS							
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		Number	Kind Code ² (if known)	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Where Relevant Passages or Relevant Figures Appear	
8	B1	2002/0052096	A1	ZHANG et al.	05-02-2002		
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50	В3	MEURIS et al., "The Relationship of the Silicon Surface Roughness and Gate Oxide Integrity in NH4OH/H202 Mixtures, Japanese Journal of Applied Physics, Vol. 31, No. 11A, Part 2, Nov. 1992, XP000414884.	
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Examiner Signature	Evan Pert	Date Considered	2-10-06

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